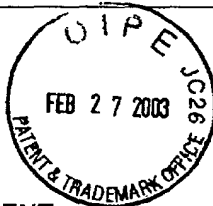


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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Applicant: Mandeep SINGH

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Page 1 of 1

Examiner: NGUYEN

Group Art Unit: 2851

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Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
HN	AR 5,433,988	07/1995	FUKUDA et al.			
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					Enclosed	No	Enclose	No
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HN	NR WO 98/28665	07/1998	PCT	LOOPSTRA et al.				
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HN	VR	Hudek et al., "E-beam and RIE examination of chemically amplified positive-tone resist CAMP6," <i>Microelectronic Engineering</i> 26:167-179 (1995), XP004000099			
HN	WR	Skulina et al., "Molybdenum/beryllium multilayer mirrors for normal incidence in the extreme ultraviolet," <i>Applied Optics</i> 34(19):3727-3730 (1995), XP000537295			
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	YR				
	ZR				
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Examiner

H. Nguyen

Date Considered:

3/8/03

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.